



Attorney Docket No.: PATENT
SSI-02001

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Maximilian Biberger et al.

Serial No.: 09/841,800

Filed: April 24, 2001

For: **METHOD OF DEPOSITING
METAL FILM AND METAL
DEPOSITION CLUSTER TOOL
INCLUDING SUPERCRITICAL
DRYING/CLEANING MODULE**

) Group Art Unit:

) Examiner:

) **TRANSMITTAL LETTER**

) 260 Sheridan Avenue, Suite 420
) Palo Alto, California 94306
) (650) 833-0160

Assistant Commissioner of Patents
Washington, D.C. 20231

Sir:

Enclosed please find an Information Disclosure Statement, Form PTO-1449 (including copies of the references contained thereon), for filing in the U.S. Patent and Trademark Office.

The Commissioner is authorized to charge any additional fee or credit any overpayment to our Deposit Account No. 08-1275. **An originally executed duplicate of this transmittal is enclosed for this purpose.**

Respectfully submitted,
HAVERSTOCK & OWENS LLP

Dated: 6-18-01

By: Thomas B. Haverstock
Thomas B. Haverstock
Reg. No.: 32,571

Attorneys for Applicants

CERTIFICATE OF MAILING (37 CFR § 1.8(a))

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HAVERSTOCK & OWENS LLP
Date: 6/18/01 By: Charles J. B...



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) **STATEMENT**

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Sir:

The citations listed below, copies attached, may be material to the examination of the above-identified application, and are therefore submitted in compliance with the duty of disclosure defined in 37 C.F.R. §§ 1.56 and 1.97. The Examiner is requested to make these citations of official record in this application.

Applicants have become aware of the following printed publications which may be material to the examination of this application:

- U.S. Patent No. 2,617,719;
- U.S. Patent No. 3,890,176;
- U.S. Patent No. 3,900,551;
- U.S. Patent No. 4,029,517;
- U.S. Patent No. 4,091,643;
- U.S. Patent No. 4,341,592;
- U.S. Patent No. 4,474,199;
- U.S. Patent No. 4,475,993;
- U.S. Patent No. 4,601,181;
- U.S. Patent No. 4,693,777;

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Date: 6/18/01 By: [Signature]



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- U.S. Patent No. 4,749,440;
- U.S. Patent No. 4,788,043;
- U.S. Patent No. 4,838,476;
- U.S. Patent No. 4,865,061;
- U.S. Patent No. 4,879,004;
- U.S. Patent No. 4,917,556;
- U.S. Patent No. 4,923,828;
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- U.S. Patent No. 5,013,366;
- U.S. Patent No. 5,068,040;
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- U.S. Patent No. 5,158,704;
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- U.S. Patent No. 5,274,129;
- U.S. Patent No. 5,288,333;
- U.S. Patent No. 5,290,361;



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This Information Disclosure Statement under 37 C.F.R. §§ 1.56 and 1.97 is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that anyone or more of these citations constitutes prior art.

Respectfully submitted,
HAVERSTOCK & OWENS LLP

Dated: 6-18-01

By: 
Thomas B. Haverstock
Reg. No.: 32,571

Attorneys for Applicants

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